



6/6/02 to 1/1/02
2/4/02
PATENTS

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

Takeo MATSUKI et al.

Serial No. 09/764,880

GROUP 2818

Filed January 23, 2001

Examiner T. Nguyen

SEMICONDUCTOR DEVICE STRUCTURE
AND METHOD FOR MANUFACTURING
THE SAME

RECEIVED
FEB - 4, 2002
TC 2800 MAIL ROOM

REQUEST TO MAKE DRAWING CORRECTION

Commissioner for Patents
Washington, D.C. 20231

Sir:

Permission is respectfully requested to amend
Figures 2B, 4, 5A, 5B, 5C and 6 of the drawings in the
above-identified application as shown in red on the
accompanying prints.

Respectfully submitted,

YOUNG & THOMPSON

By

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January 22, 2002

Fig. 2A

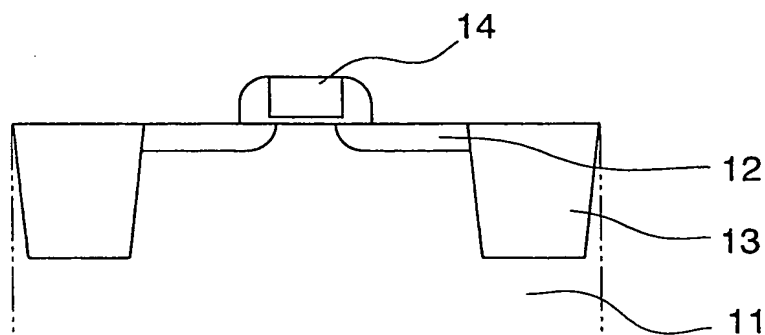


Fig. 2B

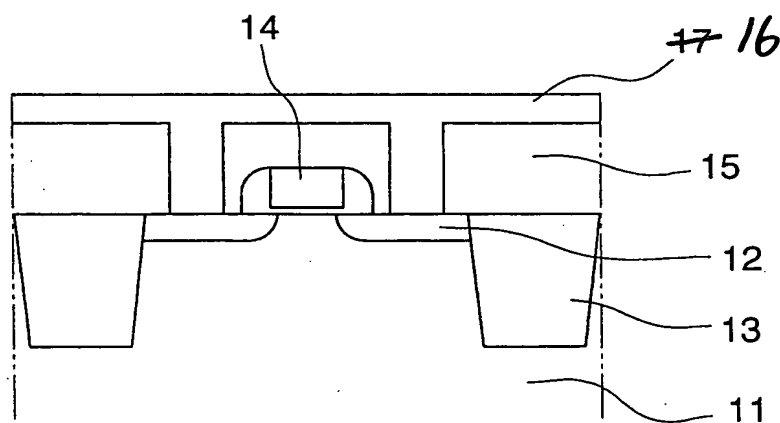


Fig. 2C

SURFACE LEVEL OF
 FIRST INSULATING FILM
 AFTER IT IS ETCHED

SURFACE LEVEL OF FIRST
 INTERLAYER INSULATING FILM AFTER
 POLYSILICON IS ETCHED BACK

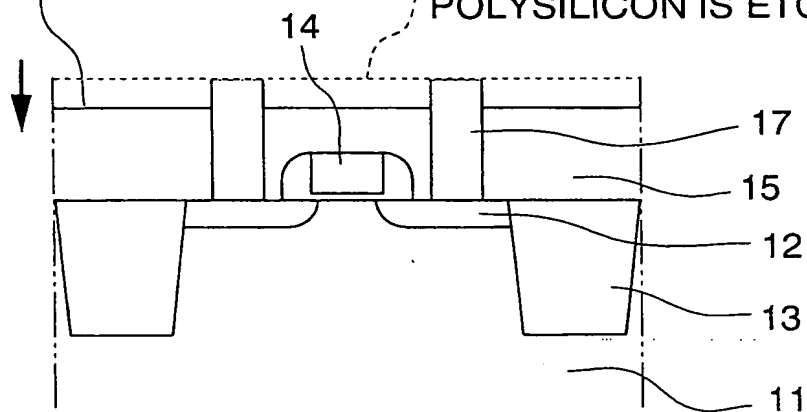


Fig. 4

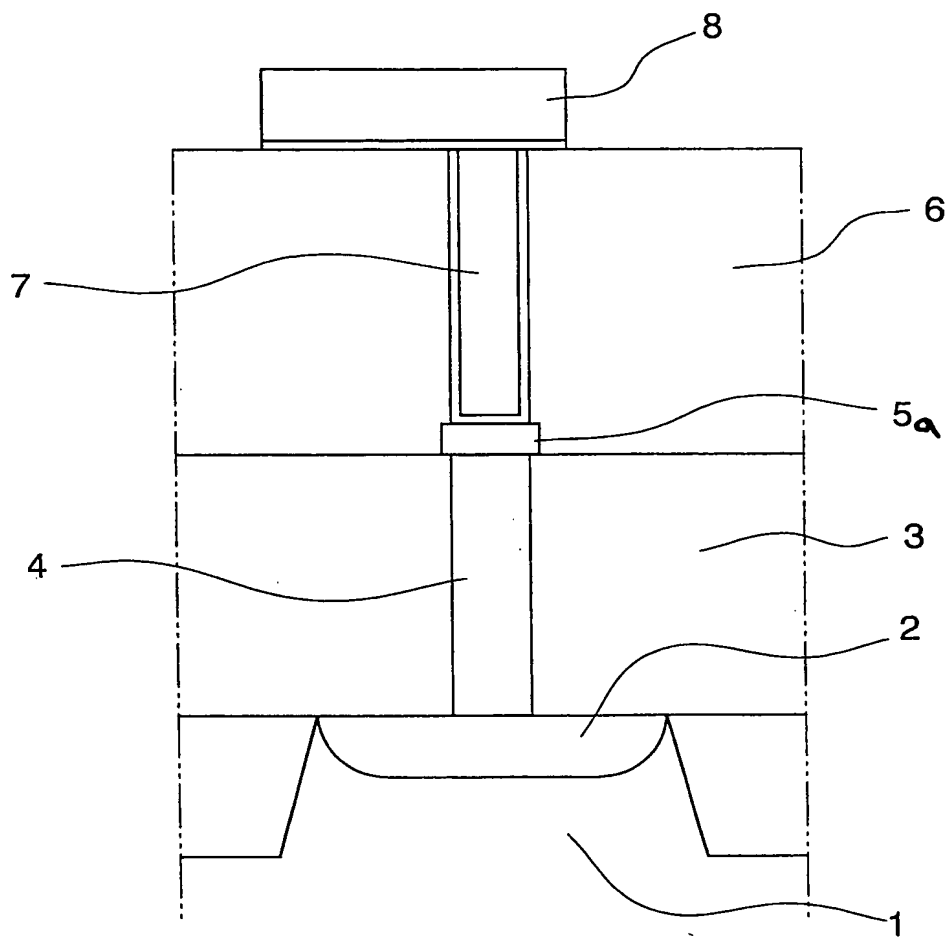


Fig. 5A (PRIOR ART)

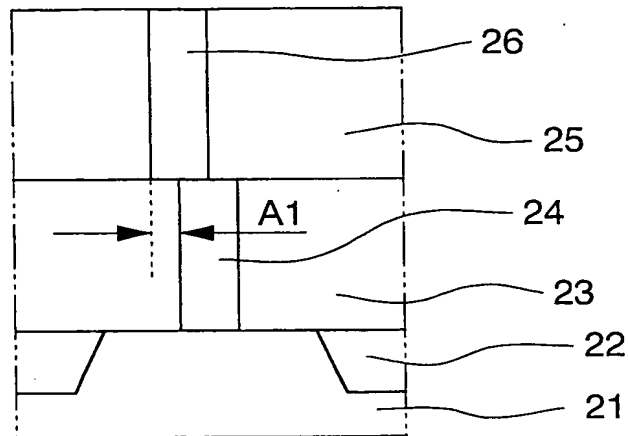


Fig. 5B (PRIOR ART)

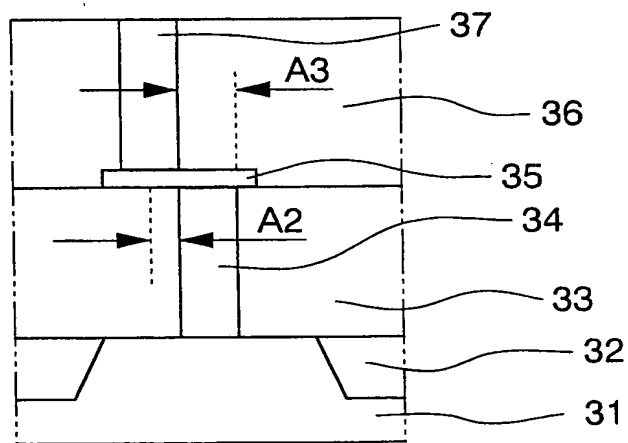


Fig. 5C (PRIOR ART)

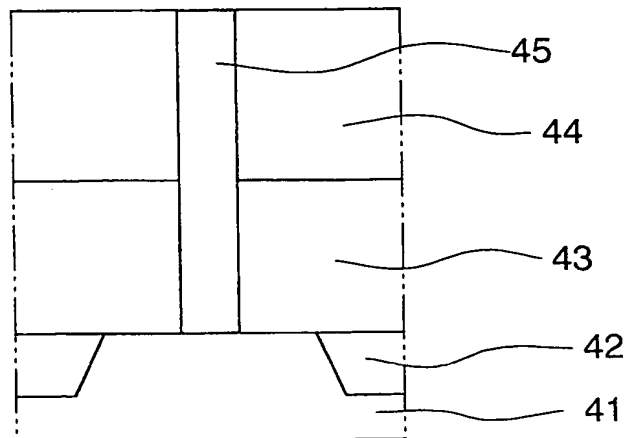


Fig. 6 (PRIOR ART)

